ATOMIC-SCALE THEORY OF RADIATION-INDUCED PHENOMENA

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THEORY OBJECTIVES

- DISPLACEMENT DAMAGE
 - > Defects, charging
 - ➢ electrons
- ROLE OF HYDROGEN, OXYGEN VACANCIES
- ALTERNATE DIELECTRICS

Interface structure, interface defects, NBTI,...

• CARRIER MOBILITIES, LEAKAGE CURRENTS

FROM ATOMIC-SCALE PHYSICS TO ENGINEERING MODELS

Atomic-scale physics: DENSITY FUNCTIONAL THEORY

- PSEUDOPOTENTIALS, SUPERCELLS
- TOTAL ENERGY, FORCES ON ATOMS
 - Stable defect configurations
 - Bulk, interface
 - Reaction energies, activation barriers
- EVOLUTION OF SYSTEM

electrons in instantaneous ground state vs

electrons allowed to evolve freely

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TALK BY M. BECK

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> electrons

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LAST YEAR: Displacement damage in silicon



<u>25 eV kick</u>

Snapshot after 100 fs

Red (hot) atoms: KE > 0.22 eV Black atoms: displaced > 0.2 Å

LOW-ENERGY RECOIL DYNAMICS IN AMORPHOUS SiO₂



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FROM ATOMIC-SCALE PHYSICS TO ENGINEERING MODELS

Amorphous Modeling





 $Si-SiO_2$ with Si-H bonds

216-atom amorphous SiO₂

ATOMIC-SCALE ROUGHNESS



Si SiO₂



OXYGEN PROTRUSION

SUBOXIDE BOND

Mobility Enhancement



Data from bulk MOSFETs or SOI MOSFETs with t>5 nm









Experiment: Zupac, Galloway, and Schrimpf, 1992

Oxygen vacancies in SiO₂





Revisit oxygen vacancies in SiO₂



ALTERNATIVE MODELS FOR E_{δ}'





Si_2 defect

Si₅ defect

Buscarino et al. 2005, 2006

Energy vs [SiSi] bond length



Isotropic Hyperfine Results



* Both Si₂ & Si₅ defects consistent with HF data

* Si₅ Defect has extra peak at 2 mT buried in central region

Atomic Structure



- Si₅ defect has one main HF active atom !
- Barrier for switching <0.6 eV

PREDICTION TO TEST: EPR AT LOW TEMPERATURE

Energy Cost/Gain to form O vacancy Clusters

• Quartz Results:

$$- E(4V_o) = 4E(V_o) + 0.05 \text{ eV} / V_o$$

• Amorphous Silica Average Results:

$$- E(4V_o) = 4E(V_o) - 0.07 \text{ eV} / V_o$$

• Amorphous Silica Minimum Results:

$$- E(4V_{o},Min) = 4E(V_{o},ave) - 0.32 eV / V_{o}$$

Energy Cost of Sub-Oxidation

A. Bongiorno and A. Pasquarello, Phys. Rev. B (2000).D. R. Hamann, Phys. Rev. B (2000).



ENERGY LEVELS OF Si₂: 0.3-0.4 eV ENERGY LEVELS OF Si₅: 1-2 eV

ENERGY LEVELS OF $\mathbf{E}'_{\tilde{a}}$: 3-4 eV



Warren et al. 1994

CONCLUSIONS ABOUT O VACANCIES

• Si_5 MODEL VIABLE FOR E_a^\prime ,

BUT MUST BE TESTED FURTHER

• LOW-TEMPERATURE EPR

• ENERGY LEVEL MEASUREMENTS